

ABSTRACT

METHODS AND APPARATUS FOR DETECTING AZIMUTHAL NON- UNIFORMITY IN A PLASMA PROCESSING SYSTEM

Apparatus and methods for assessing RF return current azimuthal uniformity are disclosed. A plurality of non-linear substantially-enclosed RF current sensors are disposed azimuthally around a central axis of a plasma processing chamber. When a plasma is ignited in the plasma processing chamber, the RF return currents are sensed in the plurality of non-linear substantially-enclosed RF current sensors and analyzed to ascertain whether RF return current azimuthal uniformity is acceptable.

FIG. 1